## Comparison Power of Semiconductor Lasers at wavelength 1480nm using InGaAs InGaAsP Materials for EDFA Pumping Scheme paper

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## Comparison Power of Semiconductor Lasers at wavelength 1480nm using InGaAs & InGaAsP Materials for EDFA Pumping Scheme

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Abstract— Long distance Optical Communications are affected by many problems; loss of signal is one of them. Erbium Doped Fiber Amplifier (EDFA) is the key to solve it. By using Semiconductor Laser as puriping source for EDFA, the signal can be brought back to it is normal condition. EDFA has a good wavelength operation at 1480nm. To achieve selected wavelength, we must construct the Semiconductor Laser that suitable in 1480nm. In that case, InGaAs and InGaAsP are the base materials to construct the Semiconductor Laser. At wavelength of 1480nm the materials that used are InGaAs and InGaAsP. The reason is it is suitable for wavelength selection. By using selected wavelength and materials, the Semiconductor Laser can be produced properly. Also, determining the parameter is the important thing to construct the Laser. By using Rate Equation, comparison of output power for InGaAs and InGaAsP at wavelength of 1480nm based on rate equation all can obtained four result. Those are injection current 1/8 voltage, carrier density, photon density and output power vs injection current. Keywords-Semiconductor Laser, Fabry-Perot, EDFA, Materials GaAs and InGaAsP

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INTRODUCTION

Light Amplification by Stimulated Emission of Radiation (LASER) has been used in many application such as telecommunication, medic of surgery, entertainment, and military and so on. The most applicable in Semiconductor Laser is Telecommunication, because Semiconductor Laser has a unique properties such as high monochromaticity, narrow spectral width and high temporal coheren As a source of light, Semiconductor Laser can be used to Erbium Doped Fiber Amplifier (EDFA) as amplifier the signal to brought back into normal condition.

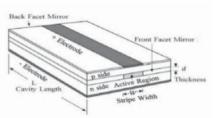


Figure 1 Semiconductor Laser Structure [5]

Due to the usage of EDFA, the applicable wavelengths is 1480nm. Since InGaAs has range of wavelength between 900nm - 1700nm, the semiconductor Laser wavelength of 1480mm is workable. In addition, for InGaAsP has range of wavelength between 1400nm-1600nm, in that case it's workable either. Basic structure of Semiconductor Laser for InGaAs and InGaAsP at 1480mm can be seen at Figure 1.

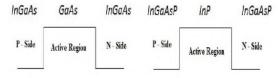


Figure 2 Structure for InGaAs and InGaAsP [1]

The length and width of Semiconductor Laser used are the same except the thickness of the active region. Calculation was based on assumption made that the Semiconductor Laser only works on the active region. Using the structure like in Figure 1. Figure 2 illustrated the differences among two materials at active region and cladding.

II. THEORY

In order to activate Semiconductor Laser it is important to formulate Rate Equation in order to obtain the 2 utput power. Rate Equation shows the prrelation between carrier density and photon density where can be expressed as [2]:

$$\frac{dn}{dt} = \frac{I}{qV_{act}} - \frac{n}{\tau_n} - G(n)S \tag{1}$$

$$\frac{dS}{dt} = G(n)S - \frac{S}{\tau_n} + \beta_{sp} \frac{n}{\tau_n}$$
 (2)

where I is injection current, q is electron charge,  $V_{cor}$  is volume of the active region,  $\tau_n$  is carrier lifetime,  $\tau_p$  is photon density,  $\beta_{sp}$  is spontaneous emission coupling factor and G(n) is stimulated emission where can be defined as:

$$G(n) = \Gamma g_0(n - n_0) \tag{3}$$

 $G(n) = \Gamma g_0(n-n) \tag{3}$  The sign of  $\Gamma$  means optical confinement factor,  $g_0$  gain slope constant, no transparency carrier density. By using Rate Equation, the expression of threshold current can be derived from the Equation (1) and (2). In steady-state, the Rate of Carrier Density  $\frac{dn}{dt}$  and the Rate of Photon Density  $\frac{dS}{dt}$  are zero and can be simplified to

$$\frac{I_{th}}{qV_{oct}} - \frac{n_{th}}{\tau_n} = 0 ag{4}$$

Where  $I_{th}$  is the threshold current and  $n_{th}$  is threshold carrier density. The value of n will be equal to  $n_{th}$ where  $I = I_{th}$ , while Injection Current reach threshold the carrier density will reach the threshold either. Rearranging Equation (4) then can be obtained

$$I_{th} = \frac{qV_{act}}{\tau_n} n_{th} \tag{5}$$

By neglecting spontaneous emission coupling factor  $\beta_{sp}$  in Equation (2) the photon density can be simplified to

$$(\Gamma g_0(n-n_0) - \frac{1}{\tau_n})S = 0$$
 (6)

Equation (6) can be arranging into Equation (7) as threshold carrier density

$$n_{th} = n_0 + \frac{1}{\Gamma \tau_p g_0} \tag{7}$$

then substitute Equation (7) into Equation (5), the threshold current can be derived into

$$I_{th} = \frac{qV_{act}}{\tau_{u}} (n_{0} + \frac{1}{\tau_{u} g_{0}})$$
 (8)

Injection current needs to activate Semiconductor Laser, in that case, must be obtained using Equation (1) and (2). Rearranging Equation (1) and (2) the equation would be

$$S = -\beta_{sp} \frac{n}{\tau_{n}} \frac{1}{G(n) - \tau_{n}^{-1}}$$
 (9)

$$I = qV_{act} \left[ G(n)S + \frac{n}{\tau_n} \right]$$
 (10)

the carrier density can be defined as

$$n = n_i \exp\left(\frac{qV}{2k_BT}\right) \tag{11}$$

where the intrinsic carrier concentration  $n_i$  can be defined as

$$n_i = 2 \left( \frac{2\pi k_B T}{h^2} \right)^{3/2} (m_e m_h)^{3/4} \exp \left( -\frac{E_g}{2k_B T} \right)$$
 (12)

By substituting Equation (11) into Equation (10) the injection current can be expressed as

$$I = qV_{act} \left[ -\beta_{sp} \frac{n_i e^{qV/2k_BT}}{\tau_n} \frac{g_0(n_i e^{qV/2k_BT})}{g_0(n_i e^{qV/2k_BT}) - \tau_p^{-1}} + \frac{n_i e^{qV/2k_BT}}{\tau_n} \right]$$
(13)

Rearranging Equation (1) and (2) will be obtained

$$\frac{I}{aV} = G(n)S + \frac{n}{\tau} \tag{14}$$

$$\frac{S}{\tau_n} = G(n)S + \beta_{sp} \frac{n}{\tau_n} \tag{15}$$

then substitute Equation (3) into Equation (14) and (15) can be formulated

$$\frac{I}{qV_{\text{ord}}} = \Gamma g_0(n - n_0)S + \frac{n}{\tau_0}$$
 (16)

$$\frac{S}{\tau_p} = \Gamma g_0(n - n_0) S + \beta_{sp} \frac{n}{\tau_n}$$
 (17)

therefore, the carrier density and photon density are given by

$$n = \frac{n_{th}}{2(1 - \beta_{co})} X - \sqrt{X^2 - Y}$$
 (18)

$$S = \frac{\beta_{sp}}{\Gamma g_0 \tau_n} \frac{X - \sqrt{X^2 - Y}}{2(1 - \beta_{sp}) - (X - \sqrt{X^2 - Y})}$$
 (19)

where the value of X and Y can be defined as [1]

$$X = 1 + \frac{I}{I_{th}} - \beta_{sp} \frac{n_0}{n_{th}}$$
 (20)

$$Y = 4(1 - \beta_{sp}) \frac{I}{I_{sh}}$$
 (21)

By substituting Equation (20) and (21) into Equation (18) and (19) we will have the final equation for carrier density and photon density as

$$n = -\frac{n_{sh} \left(\frac{I}{I_{sh}} - \sqrt{\left(\frac{I}{I_{sh}} - \frac{n_{0}\beta_{sp}}{n_{sh}} + 1\right)^{2} + \frac{I}{I_{sh}} (4\beta_{sp} - 4)} - \frac{n_{0}\beta_{sp}}{n_{sh}} + 1\right)}{2\beta_{sp} - 2}$$

$$(22)$$

$$S = \frac{\beta_{sp} \left(\frac{I}{I_{sh}} - \sqrt{\left(\frac{I}{I_{sh}} - \frac{n_{0}\beta_{sp}}{n_{sh}} + 1\right)^{2} + \frac{I}{I_{sh}} (4\beta_{sp} - 4)} - \frac{n_{0}\beta_{sp}}{n_{sh}} + 1\right)}{\Gamma g_{0} \tau_{s} \left(\sqrt{\left(\frac{I}{I_{sh}} - \frac{n_{0}\beta_{sp}}{n_{sh}} + 1\right)^{2} + \frac{I(4\beta_{sp} - 4)}{I_{sh}} - \frac{I}{I_{sh}} - 2\beta_{sp} + \frac{n_{0}\beta_{sp}}{n_{sh}} + 1\right)}$$

$$(23)$$

The Carrier Density and Photon Density have a correlation where the value of Threshold Current was same.

After finding Carrier Density and Photon Density, we will find equation of Power against Injection Current by using Photon Density in the active layer. The output power can be expressed by:

$$P = h\omega v_{g} AS \tag{24}$$

where h is Planck's constant,  $\omega$  is angular frequency,  $v_g$  is velocity group and A is area of the active region. The Output Power is the final result for this Final Project, where we can compare the output by looking at the wavelength and material.

Based on simulation, the Semiconductor Laser used in this paper are *InGaAs* and *InGaAsP* materials, the specification are listed in the tables below.

TABLE I. FIXED PARAMETERS USED FOR BOTH SHMICONDUCTOR LASER

Cavity Length L Emitter Width w	300 μm 150 μm	Temperature T  Carrier Lifetime $ au_c$	20 °C 10 ps
Voltage V	1 V	Intrinsic Carrier  Concentration $N_j$ $GaAs$	9 x 10 <sup>6</sup> cm <sup>-3</sup>
High Reflection R2	0.9	Intrinsic Carrier  Concentration $n_i$ InP	1.3 x 10 <sup>7</sup> cm <sup>-3</sup>
Partial Reflection R1	0.1	Transparency Carrier  Density $\mathcal{H}_0$	4.7 x 10 <sup>20</sup> m <sup>-3</sup>

Table I describes the fixed parameters used for the simulation. The voltage and intrinsic carrier concentration are considered to be the important parameter. Where in this paper

the voltage can be assumed to be 1 Volt for all simulation of Semiconductor Laser.

TABLE II. PARAMETER OF SEMICONDUCTOR LASER FOR INGAAS AT

Spontaneous Emission Factor β <sub>sp</sub>	8.7 x 10 <sup>-4</sup>	Velocity Group $V_g$	8.421 x 10 <sup>5</sup> cm/s
Quantum well Thickness d	75.3 Å	Photon Lifetime τ <sub>p</sub>	0. <b>294</b> ns
Volume $V_{\it act}$	3.3 x 10 <sup>-16</sup> m <sup>3</sup>	Optical Confinement Factor Γ	0.204
Агеа А	1.13 x 10 <sup>-12</sup> 7 m <sup>2</sup>	Frequency ω	1.273 x 10 <sup>6</sup> GHz

Table 2 shows the specification of *InGaAs* at 1480nm indicating that the most influential variables that can affect the output are volume of active region and frequency.

TABLE III. PARAMETER OF SEMICONDUCTOR LASER FOR INGAASP AT WAVELENGTH 1480nm

Spontaneous Emission Factor β <sub>sp</sub>	6 x 10 <sup>-1</sup>	Velocity Group $\mathcal{V}_{g}$	8.89 x 10 <sup>5</sup> cm/s
Quantum well Thickness d	140 Å	Photon Lifetime $\tau_{\mu}$	0.279 ns
Volume $V_{act}$	6.3 x 10 <sup>-16</sup> m <sup>3</sup>	Optical Confinement Factor Γ	0.224
Area A	2.1 x 10 <sup>-12</sup> m <sup>2</sup>	Frequency ω	1.273 x 10 <sup>6</sup> GHz

Table 3 shows the specification of *InGaAsP* at 1480nm indicating that the most influential variables that can affect the output are volume of active region and frequency.

The first simulation is compared injection current against voltage for both Semiconductor Laser

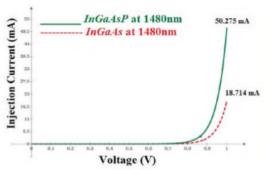


Figure 1 Comparison of Injection Current vs Voltage for InGaAs at 1480nm and InGaAsP at 1480nm

It is shown that Figure 1 shows the comparison of injection current against voltage of *InGaAs* at 1480nm and *InGaAsP* at 1480nm. The injection current for *InGaAsP* at 1480nm is

greater than InGaAs at 1480nm does. This is due to the InGaAsP at 1480nm has greater volume of active region compared to InGaAs at 1480nm. This consequently leads InGaAs at 1480nm need more Injection Current than InGaAsP at 1480nm does.

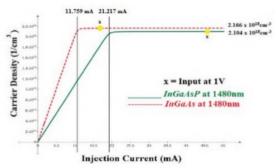


Figure 2 Comparison Carrier Density for InGaAs at 1480nm and InGaAsP at 1480nm

Figure 2 shows the comparison of carrier density against injection current between InGaAs at 1480nm and InGaAsP at 1480nm. It is shown that InGaAs at 1480nm have smaller threshold current value along injection current than InGaAsP at 1480nm does. Both were conducted at 1 volt. The main cause the differences in carrier density is due to threshold carrier density and spontaneous emission coupling factor.

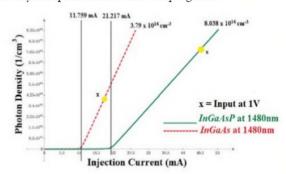


Figure 3 Comparison Photon Density for InGaAs at 1480nm and InGaAsP at 1480nm

Figure 3 shows the comparison of photon density between InGaAs at 1480nm and InGaAsP at 1480nm. It is shown that InGaAs at 1480nm has smaller threshold current than InGaAsP at 1480nm does. This leads to that the InGaAsP at 1480nm has a larger output of Photon but need more Injection Current to reach above the threshold for photon density to rise. For InGaAs at 1480nm is more efficient than InGaAsP at 1480nm, but have smaller value of photon density.

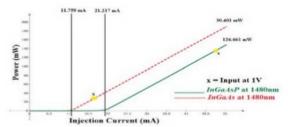


Figure 4 Comparison of Power vs Injection Current for InGaAs at 1480nm and InGaAsP at 145 nm

Figure 4 shows comparison of output power vs injects in current for InGaAs at 1480nm and InGaAsP at 1480nm. The output power vs injection current can be analyzed and compared by looking InGaAs at 1480nm and InGaAsP at 1480nm. It is shown that InGaAs at 1480nm has smaller threshold current than InGaAsP at 1480nm does. However the output Power of InGaAsP at 1480nm larger than InGaAs at 1480nm. This can be analyzed that InGaAsP at 1480nm has larger output power but not efficient compared to InGaAs at 1480nm.

TABLE IV. INGAAS AT 1480NM AND INGAASP AT 1480NM RESULT

	InGaAs at 1480nm	InGaAsP at 1480nm
Injection Current	18.714 mA	50.275 mA
Threshold Current	11.759 mA	21.217 mA
Carrier Density	2.166.10 <sup>15</sup> cm <sup>-3</sup>	2.104.10 <sup>15</sup> cm <sup>-3</sup>
Photon Density	3.79.10 <sup>16</sup> cm <sup>-3</sup>	8.5038.10 <sup>16</sup> cm <sup>-3</sup>
Output Power	30.401 mW	126.661 mW
Slope Efficiency	4.371 mW/mA	4.359 mW/mA

Looking at Table 4 above, it can be concluded that the photon density for InGaAsP are greater than InGaAs at, but the Threshold Current for InGaAs is smaller than InGaAsP. This leads InGaAsP has a larger output power than InGaAs, but InGaAs more efficient than InGaAsP because have low Threshold Current. InGaAs has larger slope efficiency than InGaAsP.



From the simulation done in this paper, it can be concluded that InGaAsP has a larger injection current at 1 volt compared InGaAsP has a larger volume than InGaAs. Meanwhile InGaAs has a larger carrier density compared to InGaAsP at 1 volt due to InGaAs has a larger threshold carrier density and spontaneous emission coupling factor. Then for InGaAsP has a larger photon density compared InGaAs due to InGaAsP has a larger spontaneous emission coupling factor. Last, for InGaAsP has a larger output power compared InGaAs, the output power can be obtained by using photon

density where the output power were influenced by area of the active region and frequency of materials. This cases are depends on parameters of Semiconductor Laser, by changing the value of fixed Parameter the new result can be obtained.

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